

Vacuum electron field emission from SnO₂ nanowhiskers annealed in N₂ and O₂ atmospheres

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The field emission properties of SnO₂ nanowhiskers were observed to change after annealing under O₂ and N₂. The electron current increased significantly from the sample annealed in N₂ and the threshold field decreased from 3.17 V/μm of the as-grown sample to 2.59 V/μm of the annealed sample. The mechanism of the field emission enhancement was explored using Fourier transform infrared spectroscopy and x-ray photoelectron spectroscopy (XPS). The results reveal that after annealing in N₂, the amount of Sn–O bonds decreased and N atoms were introduced onto the surface. The binding energies of Sn 3*d* and O 1*s* determined by high resolution XPS analysis show a shift of 0.55 and 0.47 eV, respectively, toward the high energy side. This shows that the electron emission enhancement arises from a decrease in the work function. The changes in the field emission effect from the sample annealed in O₂ are different and a possible mechanism is also proposed. © 2006 American Institute of Physics. [DOI: 10.1063/1.2161573]

Materials displaying field emission have attracted much interest because of their potential applications as cathodes in field emission displays (FEDs). One-dimensional (1D) nanostructures with high aspect ratios such as carbon nanotubes (CNT)^{1,2} are projected to be the ideal field-emission (FE) electron sources. Recently, the field emission properties of III-V and IV-IV nanowires^{3,4} and some oxide systems, such as zinc oxide⁵ and indium oxide,⁶ have also become a subject of experimental investigation. Tin oxide is useful in display devices as an anode and in gas sensors, transparent conducting electrodes, and dye-based solar cells.^{7–10} Together with other inherent properties including thermal stability, oxidation resistance, as well as large aspect ratio, one-dimensional SnO₂ nanostructures are potential FE materials.

Although our previous work has shown that SnO₂ nanowhiskers are good electron emitters,¹¹ the effects of the surface states, which are important to a good understanding of the electron emission mechanism, are, however, unclear. The surfaces of SnO₂ nanowhiskers are very active with regard to chemisorption of oxygen and other atoms due to the variable valence bands of Sn, thereby providing a useful way to change the surface chemistry by surface oxidation or introduction of surface defects.¹² Such surface modification leads to the rearrangement of the host atoms at the near surface thus changing the band structure of the SnO₂ nanowhisker system. Thermal treatment in different gas ambients is an

easy and effective way to introduce different atoms onto the surface, and past studies have shown that the annealing environment strongly impacts the structure of the SnO₂ nanoparticles.¹³ In this study, SnO₂ nanowhiskers were annealed in O₂ and N₂, and the field emission characteristics were investigated in comparison with the as-grown nanowhiskers. Fourier transform infrared spectroscopy (FTIR) and x-ray photoelectron spectroscopy (XPS) were employed to monitor the changes in the chemical bonds and atomic binding states at the surface of the SnO₂ nanowhiskers. The electron emission mechanism of the nanowhiskers is formulated based on the experimental results.

SnO₂ nanowhiskers were prepared by thermal evaporation of metallic tin and the fabrication conditions have been described elsewhere.¹¹ In order to ensure the reliability of the results, after the as-grown samples (sample A) underwent field-emission measurements in vacuum, annealing ensued in O₂ (sample B) and N₂ (sample C) at 600 °C. After annealing, the samples were immediately loaded into the field emission test chamber with a base vacuum better than 5 × 10^{−6} Pa. The samples (about 7 × 8 mm²) were affixed on a stainless-steel support to serve as the cathode. A parallel phosphor screen (anode) located at a distance of 200 μm served as the anode.

The dependence of the emission current density *J* obtained by dividing the measured current by the total apparent area of the substrate on which the emitters are grown on the applied electric field (*E*) is shown in Fig. 1(a). Relatively smooth and consistent *J*-*E* curves are obtained indicating the robustness of the emission process from our samples. The insets show the spatial distribution images of the luminescent spots on the anode of sample C at the emission fields of 4.2

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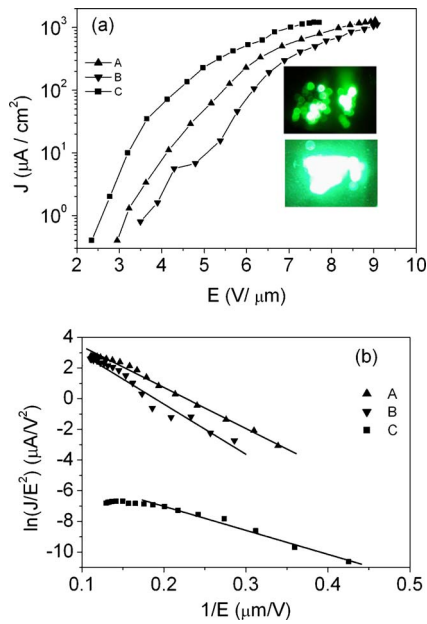


FIG. 1. (Color online) (a) Field-emission current density-field curves; (b) Fowler-Nordheim plots for both the as-grown and annealed SnO₂ nanowhiskers.

and 7.5 V/μm. The anode is lightened unevenly at 4.2 V/μm. When the field is increased to 7.5 V/μm, the anode illuminates homogeneously and brightly showing the saturated emission current. The Fowler-Nordheim (*F-N*) plots corresponding to the data in Fig. 1(a) are shown in Fig. 1(b). It exhibits a linear relationship in the range below the saturation current, indicating that the field emission process from the nanostructured SnO₂ is a barrier tunneling, quantum mechanical process (*F-N* tunneling).¹⁴

The electron emission current of the SnO₂ nanowhiskers is enhanced after annealing in N₂ but decreases slightly after annealing in O₂. The turn-on fields defined as the field required to detect a current of 1 μA/cm² are 3.17, 3.63, and 2.59 V/μm and reach 1 mA/cm² at 8.19, 8.95, and 7.04 V/μm for samples A, B, and C, respectively. The turn-on and threshold fields are comparable to the best-reported data of carbon nanotubes¹⁻³ and the tetrapod-shaped ZnO nanostructures.¹⁵

It is important to elucidate the mechanisms responsible for the field emission property changes of the SnO₂ nanowhiskers. The field emission current density J can be expressed as a function of the applied electric field E , the local work function of the emission tip Φ , and a geometric enhancement factor β to be $J \propto (\beta^2 \Phi) E^2 \exp[B\Phi^{3/2}/(BE)]$, where B is a constant.¹⁶ The parameters that govern the emission are the effective work function Φ and geometric enhancement factor β . For bulk SnO₂, Φ is estimated to be 4.3 eV.¹⁷ Hence, it is not a good field emitter. On the other hand, the one-dimensional (1D) nanostructure has a big field enhancement factor that reduces the minimal field required for effective electron emission. Moreover, the as-grown SnO₂ nanostructure is a *n*-type semiconductor and therefore a good conductive material for electrons. The parameter β describes how the electric field can be enhanced by protrusions from the emitting surface. In the *F-N* coordinates, the above equation becomes $\ln(J/E^2) \propto 1/E$, and the slope of the *F-N* plot is given by $S = -sB\Phi^{3/2}/\beta$, where s is a slope correction factor. The slopes determined from samples A, B, and

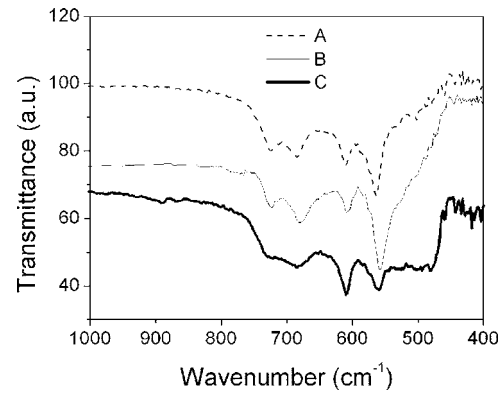


FIG. 2. FTIR spectra of both the as-grown and annealed SnO₂ nanowhiskers.

C are -24.8 , -32 , and -16.2 , respectively [Fig. 1(b)]. It suggests an increase/decrease in work function for samples B/C compared to the as-prepared sample, since the field enhancement factor β is nearly the same for these samples. As aforementioned, the emission is a barrier tunneling, quantum mechanical process. The electron field emission process involves extraction of electrons from the tin oxide nanowhiskers by tunneling through the surface potential barrier to the vacuum state. Annealing the sample in different atmospheres may change the surface structure and result in different surface potential barriers. Therefore, the chemical bonding states at the surface of the nanowhiskers were characterized by Fourier transform infrared spectroscopy (FTIR) which may provide information about surface defects after annealing.

Rutile SnO₂ belongs to the space group D_{4h}^{14} of which the normal lattice vibration at the Γ point of Brillouin zone can be given on the basis of group theory by¹⁸

$$\Gamma = A_{1g} + A_{2g} + A_{2u} + B_{1g} + B_{2g} + 2B_{1u} + E_g + 3E_u,$$

where A_{2u} and E_u are active infrared vibration modes. The FTIR spectra acquired from the SnO₂ nanowhiskers are shown in Fig. 2. In these samples, the main variable peaks appear in the range of 400 and 800 cm⁻¹. All the samples exhibit two well-defined peaks at ~ 560 and ~ 610 cm⁻¹. Two relatively weak peaks centered at 680 and 726 cm⁻¹ can be observed from samples A and B. Sample B shows the strongest and sharpest absorption peaks out of the three samples, suggesting a crystal structure with the highest quality. The 558 cm⁻¹ absorption band of the N₂ or O₂ annealed sample shifts down by 6 cm⁻¹ compared to the as-grown sample. The 610 and 678 cm⁻¹ peaks can be assigned to the transverse and longitudinal E_u modes, respectively. The two bands at 560 and 705 cm⁻¹ arise from the bending vibrations of O-Sn-O, which correspond to the A_{2u} modes.¹⁹ It can be observed that the intensities of these four absorption peaks in the spectrum of sample C decrease except for the 610 cm⁻¹ band. The 682 and 722 cm⁻¹ absorption bands transform into two broad shoulders while the 560 cm⁻¹ absorption band broadens and extends to 480 cm⁻¹. Obviously, annealing in N₂ destroys the surface stoichiometric structure and increases the structure disorder, thereby resulting in the broadened absorption bands.

To further investigate the mechanism, XPS measurements were performed on the same samples. Figures 3(a) and 3(b) show the high-resolution XPS spectra of both the as-

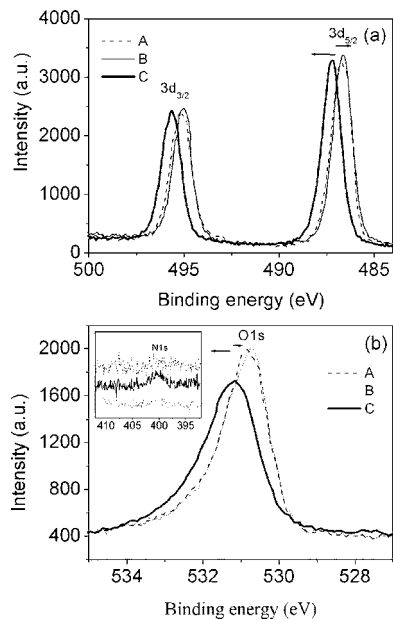


FIG. 3. High-resolution XPS spectra acquired from the as-grown and annealed SnO₂ nanowhiskers: (a) Sn 3*d* and (b) O 1*s* spectra. The insets in (b) are the N 1*s* spectra obtained from the as-grown and annealed SnO₂ nanowhiskers.

grown and annealed tin oxide nanowhiskers in the binding energy region corresponding to the Sn 3*d* and O 1*s* core levels. The peaks corresponding to the Sn 3*d* photoelectrons shift slightly toward lower binding energies in the sample annealed in O₂ and become sharper and stronger, while the peaks of the Sn 3*d* shift 0.55 eV higher in the sample annealed in N₂. With regard to O 1*s*, the peak behaves the same as that of Sn 3*d*. That is, the peaks shift 0.12 eV toward a lower binding energy in sample B but 0.47 eV toward a higher binding energy in sample C. The inset in Fig. 3(b) indicates the presence of the N 1*s* peak in sample C, showing clues that nitrogen is introduced after annealing in N₂. The atomic concentration ratios of O to Sn can be obtained by correcting the ratios of the O 1*s* and Sn 3*d* peak areas, which are 1.73, 1.76, 1.52 for samples A, B, and C, respectively, showing a 12% decrease in sample C. The full widths at half maxima (FWHM) of the Sn 3*d*_{5/2} spectra changed a little for all the samples, while the FWHM of the O 1*s* spectra changes largely in the sample annealed in N₂, increasing from 1.77 to 2.03 eV.

Considering the weakened and broadened absorption peaks in the FTIR spectra in sample C, the variations in the O 1*s* and Sn 3*d* spectra, the appearance of the N 1*s* peak, and the decrease in the O:Sn atomic ratio, it can be inferred that nitrogen is introduced into the surface of sample C to form N–O bonds. The weaker and broadened absorption bands at 682, 722, and 480 cm⁻¹ may be due to the local surface disorder caused by the new structure. The surface of sample B is reoxidized after annealing in O₂ and so the crystal quality is improved. As a result, the peaks are sharper.

It is important to note the peak of Sn 3*d* and O 1*s*. They shift 0.55 and 0.47 eV, respectively, toward higher binding energies in sample C. This means that the binding energy of the valence-band maximum (VBM) is also increased after annealing in N₂ and the decrease of VBM at the surface of the nanowhiskers suggests shifting of the Fermi level toward the vacuum level.²⁰ Consequently, the surface work function

is reduced. That is, the potential barrier the electrons have to overcome in vacuum diminishes. However, in sample B, the Sn 3*d* and O 1*s* peaks shift toward lower binding energies, indicating the formation of a more stable structure that increases the surface potential barrier and weakens the field emission behavior. This is consistent with previous reports that surface treatment by laser irradiation or plasma exposure can change the surface potential barrier height and width.^{21,22} Our experiments show that simple annealing in nitrogen can improve the field emission property of SnO₂ nanowhiskers.

In conclusion, the field emission characteristics of SnO₂ nanowhiskers annealed in N₂ and O₂ were investigated and compared to those of the as-grown ones. Analysis of the slope and intercept of the Fowler-Nordheim plots reveals that the dependence of the threshold field on the modified surface originates from the difference in the work function. Annealing in N₂ leaves the surface locally terminated with N–O bonds. This enhances emission through changing of the surface band structure thus decreasing the emission barrier or lowering the work function. Annealing in O₂ leaves a more chemically uniform surface and increases the emission barrier.

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